



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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2/8/02
C. McKinney

Applicant: Michael Weber-Grabau et al. PATENT APPLICATION
Serial No.: 09/927,102 Group Art Unit:
Filed: August 10, 2001 Examiner:
For: OPTICAL CRITICAL DIMENSION METROLOGY
SYSTEM INTEGRATED INTO SEMICONDUCTOR
WAFER PROCESS TOOL

Preliminary Amendment

Hon. Assistant Commissioner
for Patents
Washington, D.C. 20231

Sir:

Prior to a first Office action, please amend the
above-identified patent application as follows:

In the specification:

On page 1, after the title of the application and
before the subheading "TECHNICAL FIELD", please insert - -

A1
CROSS-REFERENCE TO RELATED APPLICATION

This application claims priority under 35 U.S.C.
119(e) from prior U.S. provisional application no. 60/224,571,
filed August 11, 2000. - -